Investigation of Graphene N-type Doping Effects for S/D Electrodes via Cs₂CO₃ Doping in Amorphous InGaZnO Thin-Film Transistors

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Abstract

In this work, we investigate the doping effect of single-layer graphene (SLG) used as S/D electrodes on the devices performance of amorphous InGaZnO (a-IGZO) thin-film transistors (TFTs). Control of work functions of S/D electrodes are highly demanded to improve the contact characteristics between the channel and S/D electrodes. In the a-IGZO TFTs, S/D electrodes with relatively low WF are needed because a-IGZO is an n-channel material while a p-doping of graphene is an unintentional and natural result in a transfer process via wet chemicals^[1-2]. On the other hand, n-doping of graphene requires additional materials using evaporation or wet chemical doping method. The fabricated a-IGZO TFTs with SLG S/D electrodes are dipped in the 50mM Cs₂CO₃ aqueous solution for 30 minutes to decrease the work function of SLG decreases from 4.8 eV to 4.1 eV. In the comparison of the measured transfer curves, the threshold voltage (V_{Th}) decreases from 4.4 V to 2.9 V and the extracted field-effect mobility (μ_{FE}) increases from 7.1 cm²/V-s to 10 cm²/V-s with increase of the drain current(I_{DS}) because of the improved ohmic contact between the a-IGZO layer and Cs₂CO₃ doped SLG S/D electrodes.

References

[1] X. Li, et al., *Nano Lett.*, 9.12 (2009).
[2] J. W. Suk, et al., *ACS Nano*, 5.9 (2011).



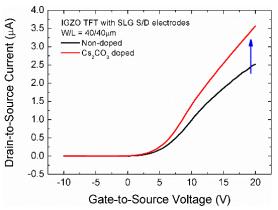


Fig 1. Representative transfer curves of the fabricated a-IGZO TFT with Cs₂CO₃ doped and nondoped SLG S/D electrodes.